CLAIMS

- 1. A method of forming a membrane for use in conjunction with a semiconductor carrier which comprises the steps of:
 - (a) providing an electrically insulating substrate;
 - (b) forming an interconnect pattern on said substrate;
- (c) forming a stud coupled to said interconnect pattern over said substrate by forming a gold ball and coating a portion of said gold ball with a compliant material.
- 2. The method of claim 1 wherein step (c) includes the steps of forming said gold ball by forming a ball bond on said substrate.
- 3. The method of claim 1 wherein said step of coating said gold ball includes the step of immersing a portion of said ball into a compliant epoxy resin to coat said ball with said compliant material.
- 4. The method of claim 2 wherein said step of coating said gold ball includes the step of immersing a portion of said ball into a compliant epoxy resin to coat said ball with said compliant material.
- 5. The method of claim 1 wherein said compliant material is filled with a material having sufficient hardness to be capable of penetrating the oxide film on the contact pads of semiconductor devices.

- 6. The method of claim 2 wherein said compliant material is filled with a material having sufficient hardness to be capable of penetrating the oxide film on the contact pads of semiconductor devices.
- 7. The method of claim 3 wherein said compliant material is filled with a material having sufficient hardness to be capable of penetrating the oxide film on the contact pads of semiconductor devices.
- 8. The method of claim 4 wherein said compliant material is filled with a material having sufficient hardness to be capable of penetrating the oxide film on the contact pads of semiconductor devices.
 - 9. The method of claim 5 wherein said material is silver or silver-based flakes.
 - 10. The method of claim 6 wherein said material is silver or silver-based flakes
 - 11. The method of claim 7 wherein said material is silver or silver-based flakes
 - 12. The method of claim 8 wherein said material is silver or silver-based flakes
- 13. A membrane for use in conjunction with a semiconductor carrier which comprises:
 - (a) an electrically insulating substrate;
 - (b) an interconnect pattern on said substrate;
- (c) a stud coupled to said interconnect pattern over said substrate, said stud comprising a gold ball and a compliant material coating over a portion of said gold ball.

- 14. The membrane of claim 13 wherein said gold ball is the ball of a ball bond on said substrate.
 - 15. The membrane of claim 13 wherein said coating is a compliant epoxy resin.
 - 16. The membrane of claim 14 wherein said coating is a compliant epoxy resin.
- 17. The membrane of claim 15 wherein said compliant material is filled with a material having sufficient hardness to be capable of penetrating the oxide film on the contact pads of semiconductor devices.
- 18. The membrane of claim 16 wherein said compliant material is filled with a material having sufficient hardness to be capable of penetrating the oxide film on the contact pads of semiconductor devices.
- 19. The membrane of claim 17 wherein said material is silver or silver-based flakes.
- 20. The membrane of claim 18 wherein said material is silver or silver-based flakes.